

Application/Control No.	Applicant(s)/Patent under Reexamination	
10/558,057	HWANG ET AL.	
Examiner	Art Unit	
HERBERT J. LILLING	1657	

SEARCHED					
Class	Subclass	Date	Examiner		
435	128	12/26/2007	HJL		
435	130	12/26/2007	HJL		
435	155	12/26/2007	HJL		
435	156	12/26/2007	HJL		
435	158 .	12/26/2007	HJL		
			WEST		

SEARCH NOTES (INCLUDING SEARCH STRATEGY)					
	DATE	EXMR			
	12/26/2007	HJL			
h History					
Clear Cancel					

: Monday, December 24, 2007

<u>Set</u> Name	Query	Count					
B=PG	SPB,USPT,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ	0					
L8	l6 and lipase and (trityl or nosyl or t-butyl or butyl)	0					
L7	l6 and lipase and (trityl or nosyl or t-butyl or tertiary butyl)	()					
L6 L5	L5 and racemic diol  1,2 diol and lipase and anhydride and optical	135					
L3	4996158.pn. and (trityl or nosyl or t-butyl or tertiary butyl or trityl) 4996158.pn. and succinic anhydride and lipase and (trityl or nosyl or t-butyl or tertiary butyl or trityl)						
L3							
L2	4996158.pn. and succinic anhydride and lipase						
-L1	4996158	24					
	APPLICANTS						
	Soon Ook Hwang, Daejeon, KOREA, REPUBLIC OF; Do Hoon Kim, Daejeon, KOREA, REPUBLIC OF; Hye Youn Ryu, Daejeon, KOREA, REPUBLIC OF;						
	Tae Im Lee, Daejeon, KOREA, REPUBLIC OF; Sun Ho Chung, Daejeon, KOREA, REPUBLIC OF						

Restore

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